

Supporting Information

Unusual Interfacial Freezing Phenomena in Hexacontane/Silica Composites

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Experimental section

1. Surface modification of Stöber silica particles

Prior to the surface functionalization of SiO₂, the dry SiO₂ nanoparticles were treated with piranha solution for 4 h at room temperature in order to activate the –OH groups on the nanoparticle surface. After removal from the solution, the powders were rinsed copiously with deionized water, and then dried at 110 °C overnight to remove physical adsorbed water on silica surface.

1 g of activated silica was added into 100 ml of anhydrous toluene and the mixture was stirred at 120 °C for 2 h. Then, 0.5 g of 3-Aminopropyltriethoxysilane (APTES, Sigma-Aldrich) was introduced into the mixture and reacted for 24 h at 120 °C under a dry nitrogen atmosphere. The mixture was centrifuged to obtain silica nanoparticles. To remove the unreacted organosilane, the silica powders were washed with toluene, ethanol and methanol successively. Modified silica samples were then dried at 110 °C in a vacuum oven for 12 h before further used.

2. Preparation of C₆₀H₁₂₂/modified silica composites

To ensure the homogeneities of samples, solution mixing method was applied to prepare the C₆₀H₁₂₂/modified SiO₂ composites. Firstly, C₆₀H₁₂₂ was dissolved in toluene at 70 °C, and SiO₂ particles were well-dispersed in toluene with sonication. Then the two solutions were mixed with desired volume to achieve the composites with different silica weight loadings and stirred for 24 h at 70 °C. Eventually, the composite specimens were obtained through solvent evaporation and subsequently dried under vacuum at 50 °C for 12 h.

3. Characterization.

Temperature-dependent X-ray diffraction (XRD) experiments were performed on an X'Pert Pro MPD X-ray diffractometer with the temperature region similar to that for DSC measurements, using Cu K α radiation (1.54 Å), power of 40 mA/40 kV, and rotating angle $2\theta = 5\text{--}40^\circ$. The heating and cooling rates were all 2 °C/min, and at each temperature point, the samples were equilibrated for about 5 min before data collection.

Differential scanning calorimetry (DSC) measurements were performed with a Q2000 (TA Instruments) in the temperature range of 80~110 °C under nitrogen atmosphere. In order to ensure the reproducibility, two or three measurements were recorded for each sample.

The grazing incidence X-ray diffraction (GIXD) measurements of the *n*-alkane film structure were carried out on a Xeuss SAXS/WAXS system (Xenocs SA, France). To do the temperature-dependent GIXD measurement, a Linkam thermal stage was used for temperature control. A multilayer focused Cu K α X-ray source (GeniX3D Cu ULD), generated at 50 kV and 0.6 mA, was utilized. The wavelength of the X-ray radiation was 0.15418 nm. A semiconductor detector (Pilatus 300 K, DECTRIS, Swiss) with a resolution of 487×195 pixels (pixel size = 172×172 μm^2) was applied to collect the scattering signals. Each GIXD pattern was collected with an exposure time of 600 seconds. The incident beam made an angle of $\sim 0.1^\circ$ with the SiO₂ surface.

The proton NMR magnetization relaxation study was carried out on a 400 MHz

Bruker spectrometer by standard Carr–Purcell–Meiboom–Gill (CPMG) pulse sequence at 378 K. A $\pi/2$ pulse width of 5 μs was used for ^1H NMR experiments. The recycle delay time was 5 s. The adamantane ($\text{C}_{10}\text{H}_{16}$) at 1.91 ppm was taken as reference.

Results

The phase transition of $C_{60}H_{122}/SiO_2$ composites was characterized by variable-temperature XRD as shown in Figure S1. When the temperature decreases to the crystallization temperature ($99\text{ }^{\circ}C$), two diffraction peaks at $2\theta = 21.3^{\circ}$ and 23° corresponding to the (110) and (200) planes of the orthorhombic crystal appear.

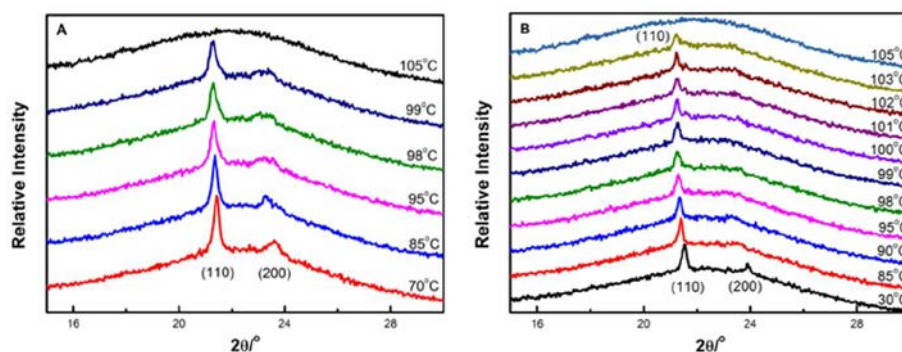


Figure S1. Variable-temperature XRD patterns of $C_{60}H_{122}/SiO_2$ composites with $\phi_{C_{60}H_{122}}=10\%$ both during cooling (A) and heating (B) process.

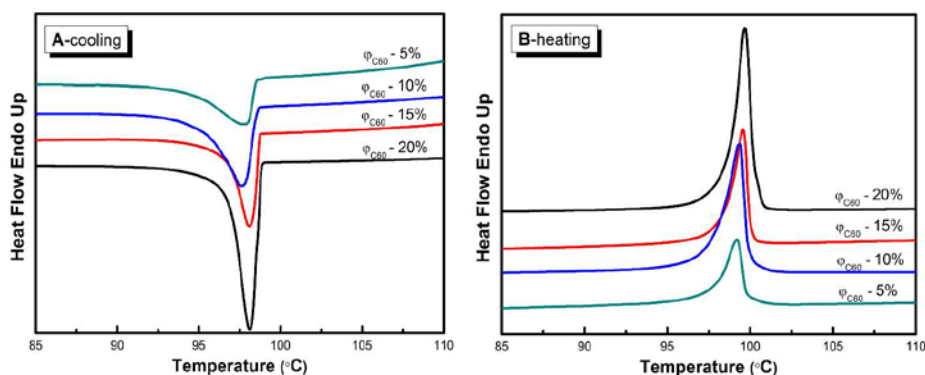


Figure S2. DSC curves of $C_{60}H_{122}/$ modified SiO_2 composites during cooling (A) and heating (B) processes.

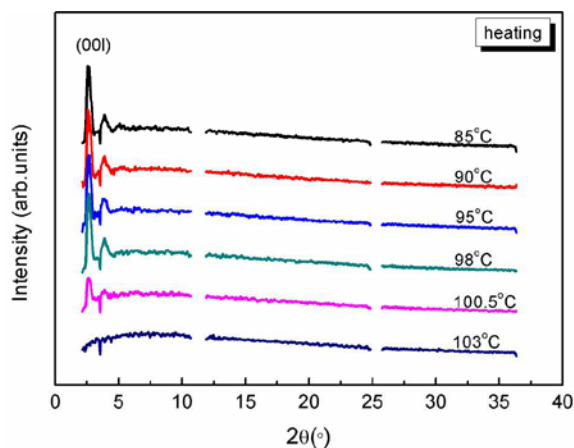


Figure S3. Variable-temperature grazing-incidence X-ray diffraction patterns of C₆₀H₁₂₂ thin film adsorbed on the silicon wafer during heating process.

Proton NMR relaxation experiments were performed to investigate the molecular dynamics of C₆₀H₁₂₂. The ¹H NMR spectra of the pure C₆₀H₁₂₂ and C₆₀H₁₂₂/SiO₂ composites are displayed in Figure S4. There are two characteristic resonance peaks at ~0.99 ppm for terminal methyl group (CH₃), ~1.40 ppm for CH₂ group of C₆₀H₁₂₂.¹ The ¹H transverse relaxation times (*T*₂) of above two parts were measured and the relaxation data are shown in Table S1. *T*₂ values could be extracted by fitting magnetization relaxation model using the following function:²

$$I(t) = I(0) \cdot \exp(-t / T_2)$$

where *I*(*t*) is the signal intensity, *I*(0) is the intensity at *t* = 0. For the CH₂ proton relaxation, the decay time, *T*₂, is 377.35 ms for pure C₆₀H₁₂₂, but the composites show the short decay time, *T*₂ = 38.33 and 30.08 ms for C₆₀H₁₂₂/SiO₂ composite with φ_{C₆₀H₁₂₂} = 10 and 3 wt %, respectively. It has been reported that the larger the amplitude of chain motions is, the longer the *T*₂ will be.³

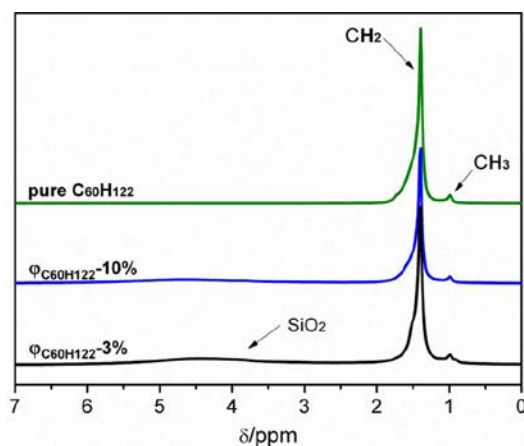


Figure S4. ^1H NMR spectra of $\text{C}_{60}\text{H}_{122}/\text{SiO}_2$ composites with various compositions at 378 K, the percentage inset is for $\phi_{\text{C}_{60}\text{H}_{122}}$.

Table S1 T_2 values of the proton of CH_2 and CH_3 of pure $\text{C}_{60}\text{H}_{122}$ and $\text{C}_{60}\text{H}_{122}/\text{SiO}_2$ composites

Sample	CH_2 T_2 (ms)	CH_3 T_2 (ms)
Pure $\text{C}_{60}\text{H}_{122}$	377.35	438.60
Composite-10wt%	38.33	44.31
Composite-3wt%	30.08	34.98

References

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